Halogenodisilanes

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The syntheses of bromo-, chloro-, and fluoro-disilanes are reported, and the preliminary identification of 1-bromo-1-chlorodisilane and 1-bromo-1,1-dichlorodisilane. The ¹H and ¹⁹F n.m.r. parameters of these and related compounds are reported and discussed.

THE formation of chloro- and bromo-disilanes by direct reaction of disilane with boron trichloride 1 and tribromide 2 has been described in preliminary communications. We have extended this work and also report the identification of some fluorodisilanes and mixed halogen species. The ¹H and ¹⁹F n.m.r. parameters for these compounds are presented because only limited chemical-shift data have been reported. 1-3 The values of the 29Si-H coupling constants in these and related disilanyl derivatives are correlated with the 'effective electronegativity' by a quadratic function similar to that used with monosilanes.4

EXPERIMENTAL

Disilane was prepared by the lithium tetrahydroaluminate reduction of hexachlorodisilane.⁵ Commercial Viton A diaphragm) which was used for all experiments. The ¹H n.m.r. spectra were recorded on a Varian A 60 highresolution variable-temperature spectrometer and the ¹⁹F n.m.r. spectra on a Varian HA 100 high-resolution spectrometer. The n.m.r. parameters are listed (Table 1) along with those of related compounds (Table 2).

Formation of Monochlorodisilane.—Typically, Si₂H₆ (4.5 mmoles) was condensed at -196° with BCl₃ (1.5 mmoles) into a reaction vessel (ca. 60 ml) and then held at 0° for 8 h. The product was fractionated by trap-to-trap distillation through a trap at -63° into one at -96° to give Si₂H₅Cl (1·7 mmoles).

Formation of 1,1- and 1,2-Dichlorodisilane.—Typically, Si₂H₆ (4.5 mmoles) and BCl₃ (2.25 mmoles) were allowed to react as described in the previous experiment. Trap-totrap distillations gave the dichlorodisilanes (1.8 mmoles) from a trap at -45° . The ¹H n.m.r. spectrum was recorded immediately and confirmed the presence of both

TABLE 1 ¹H N.m.r. parameters for halogenated disilanes

				1		$J(^{29}SiH_2)$		$J(^{29}{ m SiH_2})$ or		
C	$\delta(SiH_3)$	δ(SiH ₂)	δ(SiH)	J(HH)	J(29SiH ₃)	$J(^{29}SiH)$	$J(^{29}SiH_2)$ calc.	$J(^{29}SiH)$ calc.	/(H-M-MF)	J(H-MF)
Compound		·	0(3111)		0 1			-221·7	J(II III IIII)	J (III MIII)
SiH ₃ ·SiH ₂ Cl ^a SiH ₃ ·SiHCl ₂	$\frac{3.47}{3.53}$	4.82	5.70	${3\cdot 0}\atop 2\cdot 1$	$-201 \cdot 4 \\ -210 \cdot 0$	$-221 \cdot 2$ $-266 \cdot 3$	$-203.8 \\ -209.5$	-221.7 -270.5		
SiH ₃ ·SiCl ₃	3.65		0.0		-214.0	2000	-215.0			
SiH,Cl·SiH,Cl	5 55	4.80		$3 \cdot 0$		-233.0		$-227 \cdot 3$		
SiH2Cl·SiHCl2		4.79	5.75	$3 \cdot 0$		-237.2		-232.9		
_				_		(-276.6)		$-276 \cdot 1$		
SiHCl ₂ ·SiHCl ₂			5.70	b		-280.2		-281.7		
SiH₃•SiH₂Br ¢	3.61	4.31		$3 \cdot 0$	-202.6	-225.8	-203.9	-221.9		
SiH ₃ ·SiHBr ₂	3.90		$5 \cdot 42$	$2 \cdot 3$	-210.0	-254.2	-209.6	$-271 \cdot 4$		
SiH ₃ ·SiBr ₃	4.59	4.40		• •	b	202.4		005 5		
SiH ₂ Br·SiH ₂ Br		4.48	5.43	3.0		$-236.4 \\ -242.0$		$-227.5 \\ -233.2$		
SiH ₂ Br·SiHBr ₂ SiHBr ₂ ·SiHBr ₂		4.56	5·43 5·40	9.0		b		233.2		
	0.10	~ 00	0 40	2.5	7			999.0	0.0	40.0
SiH ₃ SiH ₂ F ^d	3.19	5.30		$2 \cdot 7 \\ 2 \cdot 8$	$^{b}_{-206\cdot 2}$	-217	-210.2	-222.8	6·6 6	$\substack{\textbf{43} \cdot \textbf{2} \\ \textbf{53}}$
SiH ₃ SiHF ₂ SiH ₃ SiF ₃	$\frac{3.28}{3.35}$	5.40		2.0	200·2 b	U	-210.2		5·8	99
GeH ₃ SiHF ₂ ¢	2.72	4.96		3.0	b	ь			8.0	54.5
OULIGORAL 2	for Ge				_	_			- 4	
SiH ₃ SiH ₂ If	3.66	3.39		3.0	-204.6	-224.0	$-202 \cdot 8$	-217.8		
SiH ₃ SiHClBr SiH ₃ SiCl ₂ Br	$\begin{array}{c} 3.66 \\ 3.80 \end{array}$		5.66	$2 \cdot 25$	$-208\cdot0$	b	-209.5			

^a A. D. Craig, J. V. Vrenovitch, and A. G. MacDiarmid, *J. Chem. Soc.*, 1962, 548. ^b Not measured, owing to either insufficient concentration or peaks being masked by solvent or compound peaks. ^c M. Abedini, C. H. Van Dyke, and A. G. MacDiarmid, *J. Inorg. Nuclear Chem.*, 1963, 25, 307. ^d M. Abedini, Ph.D. Thesis, University of Pennsylvania, 1963. ^e Ref. 14. ^f L. G. L. Ward and A. G. MacDiarmid, J. Amer. Chem. Soc., 1960, 82, 2151.

The values for the chlorodisilanes agree with those reported, when corrected with reference to tetramethylsilane as internal standard. All figures for chemical shifts are relative to internal T.M.S. A downfield shift is considered to be positive.

samples of boron trichloride and tribromide were purified by distillation in a conventional Pyrex-glass vacuum line fitted with greaseless stopcocks (Springham and Co.;

- ¹ J. E. Drake and N. Goddard, Inorg. Nuclear Chem. Letters,
- 1968, 4, 385.

 ² J. E. Drake and J. Simpson, Inorg. Nuclear Chem. Letters 1966, 2, 219.

SiHCl₂·SiH₃ (5%) and SiH₂Cl·SiH₂Cl (95%). After ½ h at room temperature the spectrum showed 95% SiHCl₂·SiH₃.

- 3 A. G. MacDiarmid and M. Abedini, Inorg. Chem., 1963, 2,
- 608.

 4 M. A. Jensen, J. Organometallic Chem., 1968, 11, 423. ⁵ G. W. Bethke and M. K. Wilson, J. Chem. Phys., 1957, 26, 1107.

J. Chem. Soc. (A), 1970

The i.r. spectra of these chloro-compounds were as reported earlier 6 and further confirmation was provided by their Raman spectra. The main features in the Raman effect are shown (Table 3) along with those of SiHF₂·SiH₃.

Formation of 1,1,2-Trichlorodisilane and 1,1,2,2-Tetrachlorodisilane.—Typically, Si₂H₆ (4.5 mmoles) and BCl₃ (4.5 mmoles) were allowed to react as described in the previous experiment. Fractionation gave SiHCl₂·SiH₂Cl described earlier. After 1 h at room temperature the Si₂H₆ (2·1 mmoles) was recovered.

Formation of 1,1,1-Trifluorodisilane.—Typically, SiHCl₂-- SiH_3 (1.0 mmole) was passed at room temperature over SbF₃ (5 g) supported on glass wool. The volatile constituents were distilled back and forth through the SbF₃ for 5 min and then fractionated, to give a mixture of SiF4 and Si₂F₆ (0.52 mmole; identified by i.r. spectra 7,9)

TABLE 2 ¹H N.m.r. parameters of disilanyl derivatives

				$J(^{29}\mathrm{SiH_3})$	$J(^{29}{ m SiH_2})$ or	$J(^{29}\mathrm{SiH}_2)$ or
	(SiH_3)	(SiH_2)	$J(^{29}\mathrm{SiH_3})$	calc.	$J(^{29}\mathrm{SiH})$	J(SiH) calc.
SiH₃•SiH₃ ^a	3.25		-198.4			
SiH ₃ ·SiH ₂ ·SiH ₃ ^a	3.38	3.20	-199.0	-197.0	$-193 \cdot 1$	-181.4
$SiH_3 \cdot SiH(SiH_3)_2 b$	3.40	2.91	-192 ± 5	-195.7	c	
SiH ₃ ·SiH ₂ ·SiH ₂ ·SiH ₃ b	3.34	3.24	-199 $^{-}$	-197.0	-197.0	-181.4
SiH ₃ ·SiH ₂ Me ^d	3.17	3.67	-191.0	-195.0	-189.0	$-185 \cdot 1$
SiH ₃ ·SiH ₂ ·PH ₂ ·	3.19	3.57	-201.0	-198.8	с	
$(SiH_3 \cdot SiH_2)_3 P^{\bar{f}}$	3.40	3.98	c		c	
SiH ₃ ·SiH ₂ ·AsH ₂ ^g	3.45	3.60	-201.0	h	c	
SiH ₃ ·SiH·NMe ₂ d	3.15	4.74	c		-199.8	$-199 \cdot 4$
$SiH_3 \cdot SiH_2 (NMe_2)_2 d$	3.30	5.00	-184.5	$-200 \cdot 4$	c	
$(SiH_3 \cdot SiH_2)$, NMe d	3.19	4.78	С		-203.0	-203.5
$(SiH_3\cdot SiH_2)_3N^d$	3.28	4.84	c		-205.2	-203.5
SiH ₃ ·SiH ₂ ·O·SiH ₃ ·	3.22	5.13	-192.8	$-202 \cdot 1$	-210.6	$-215 \cdot 1$
SiH ₃ ·SiH ₂ ·OMe ⁱ	$3 \cdot 17$	4.99	-198.2	-201.6	-207.6	$-215 \cdot 1$
(SiH ₃ •SiH ₂) ₂ O ^b	3.20	5.12	-194.4	$-201 \cdot 1$	-214.8	$-215 \cdot 1$
$(SiH_3 \cdot SiH_2)_2 S^j$	3.39	4.55	-202.0	-201.3	-213.6	-210.8

^a E. A. V. Ebsworth and J. J. Turner, Trans. Faraday Soc., 1964, 60, 256. ^b S. D. Gokhale and W. L. Jolly, Inorg. Chem., 1964, 3, 946. ^c Not measured. ^d Footnote d of Table 1. ^e S. D. Gokhale and W. L. Jolly, Inorg. Chem., 1965, 4, 597. ^f J. E. Drake and N. Goddard, J. Chem. Soc. (A), 1969, 662. J. E. Drake, N. Goddard, and J. Simpson, Inorg. Nuclear Chem. Letters, 1968, 4, 361. C. H. Van Dyke, Ph.D. Thesis, University of Pennsylvania, 1964. L. G. L. Ward and A. G. MacDiarmid, J. Inorg. Nuclear Chem., 1962, 21, 287.

(1.8 mmoles) from a trap at -23° ; SiHCl₂·SiHCl₂ (ca. 0.2) mmole) was retained in the trap at that temperature.

Formation of 1,1-Diffuorodisilane.—Typically, SiHCl2 SiH3 (2.2 mmoles) was condensed at -196° in the reaction vessel which contained SbF₃ (5 g) supported on glass-wool. The vessel was warmed to room temperature and the volatile contents distilled out leaving an antimony mirror. Noncondensable gases (0.2 mmole) were pumped away and the

TABLE 3

Main features in the Raman spectrum of some halogenodisilanes (cm⁻¹)

 $SiH_3 \cdot SiH_2Cl SiH_3 \cdot SiHCl_2 SiH_2Cl \cdot SiH_2Cl SiH_3 \cdot SiHF_2$ 2198s(pol) Si-H str 2186s(pol) 2162s(pol) 2183s(pol) Si-Cl str 538m 536m 554m 418s(pol) 397s(pol)410s(pol) 426s(pol) Si-Si str (s = strong, m = medium, pol = polarised.)

remaining volatile constituents fractionated through a trap at -96° into one at -196°. The latter contained SiF₄ and SiH₄ (total 0.9 mmoles; identified by i.r. spectra 7,8) and the former $\mathrm{SiHF_2\text{-}SiH_3}$ (1.73 mmoles), identified by $^1\mathrm{H}$ and ¹⁹F n.m.r. spectra (Table 1 and Discussion section). The i.r. spectrum of SiHF₂·SiH₃ showed peaks at 2185s, 2175s, 2150sh, 948w, 940m, 930m, 910sh, 825sh, 815vs, and 523w cm⁻¹; the main features in its Raman spectrum are shown in Table 3.

Experiments were also carried out in which Si₂H₆ (typically 2·1 mmoles) was condensed on SbF₃ (5 g) as containing a trace of SiF₃·SiH₃ and SiHCl₂·SiH₃ (0·2 mmole) with involatile materials.

ofFormation 1-Bromo-1-chlorodisilane.—Typically Si₂H₅Cl (1·0 mmole) and BBr₃ (0·4 mmole) were condensed at -196° into the 60 ml reaction vessel and held at 0° for 8 h. The noncondensable products were pumped away at -196° and the remaining volatile products fractionated to give SiH₄ and B₂H₆ (total 0.25 mmole; identified by i.r. spectra 8,10), Si₂H₅Cl (0.6 mmole), and SiHCl₂·SiH₃ and SiHBrCl·SiH₃ (total 0·3 mmole; estimated from integrated ¹H n.m.r. spectrum to be in the ratio 1:1).

Formation of 1-Bromo-1,1-dichlorodisilane.—Typically, SiHCl₂·SiH₃ (0·75 mmoles) and BBr₃ (0·13 mmole) were condensed together at -196° into the 60 ml reaction vessel and then maintained at 0° for 6 h. After recooling to -196° the noncondensable gases (0·12 mmole) were pumped away. Fractionation gave SiH_4 and B_2H_6 in a trap at -196° . A trap at -126° contained 0.3 mmole of volatile products identified by the ¹H n.m.r. spectrum as a mixture of SiBrCl₂·SiH₃, SiHCl₂·SiH₃, and SiCl₃·SiH₃ in the ratio ca. $1:1:0\cdot 1$. In another series of experiments, BCl_3 (typically 0.2 mmole) was condensed at -196° with a 1:1 mixture of Si₂H₅Br and Si₂H₄Br₂ (a total of 0.8 mmole) and held at 0° for 6 h. There was a considerable amount of nonvolatile deposit and fractionation of the volatile products gave SiH₄ and B₂H₆ (total 0.2 mmole) and only unreacted starting material containing a trace of SiHBrCl·SiH₃ (total 0.3 mmole) in a trap at -126° . There was no evidence for the presence of any species such as Si₂H₃Br₂Cl.

⁶ R. P. Hollandsworth and M. A. Ring, Inorg. Chem., 1968,

<sup>7, 1635.
7</sup> P. J. H. Woltz, E. A. Jones, and H. H. Nielsen, *Phys. Rev.*, 1950, **79**, 416.

⁸ C. H. Tindal, J. W. Straley, and H. H. Nielsen, Phys. Rev., 1942, 62, 151.

⁹ E. A. Samworth, Ph.D. Thesis, John Hopkins University, 1963.

¹⁰ R. C. Lord and I. Shapiro, J. Chem. Phys., 1951, 19, 1.

Formation of Monobromodisilane.—Typically, Si₂H₆ (1.5 mmoles) and BBr₃ (0.3 mmole) were condensed at -196° in a 60 ml reaction vessel and maintained at 0° for 8 h. The products were fractionated and Si₂H₅Br (0.25 mmole) passed through a trap at -63° , leaving behind higherbrominated disilanes.

Formation of 1,1- and 1,2-Dibromodisilane.—Typically, Si₂H₆ (1·2 mmoles) was condensed and allowed to react with BBr₃ (0.4 mmole) as described in the previous experiment. Fractionation gave Si₂H₅Br (0·1 mmole) and a mixture of SiHBr, SiH, and SiH, Br SiH, Br (0.2 mmole) in the ratio 5:95 as shown by the ¹H n.m.r. spectrum which was recorded immediately after the separation. There was no evidence of a change in the ratio of these components with

Formation of Polybromodisilanes.—Typically, Si₂H₆ (1.4 mmoles) and BBr₃ (0.7 mmole) were condensed at -196° into a 165 ml reaction vessel and held for 8 h at 0°. Fractionation of the products gave Si₂H₅Br (0·1 mmole), Si₂H₄Br₂ (0.05 mmole), and SiH₂Br·SiHBr₂ (0.4 mmole). The tribromodisilane was collected in a trap at -23° while the 1,1,2,2-tetrabromodisilane (0.15 mmole) was retained in a trap at 0°.

DISCUSSION

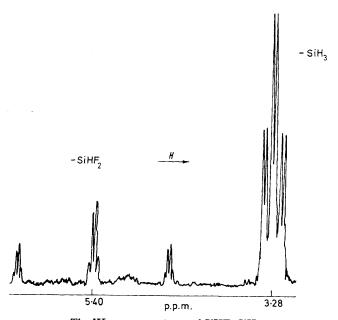
The reduction of boron trichloride and tribromide to diborane by disilane takes place fairly readily, both reactions showing similar features. The formation of monohalogenodisilanes is best carried out with a ratio of BX_3 to Si_2H_6 of $\leq 1:3$. An increase in the relative amount of BX₃ leads to more halogenation of disilane with less percentage conversion to mono- and more to poly-halogenodisilanes. If it is increased still further eventually only polyhalogenosilanes of an intractable nature are formed. The size of reaction vessels is fairly important since too low a pressure gives very little conversion of the disilane and too high a pressure leads to a large amount of intractable materials.

The tendency of halogenodisilanes to both isomerisation and decomposition has been noted for the chloro-11 and for the bromo-disilanes 12 and attributed to the presence of Lewis acids. We find that there is rapid isomerisation of 1,2- to 1,1-dichlorodisilane while stored samples of mixtures of chlorodisilanes give small amounts of 1,1,1-trichlorodisilane as they slowly decompose. The preparation of bromodisilanes from the aluminium tribromide-catalysed reaction of hydrogen bromide on disilane yielded 1,1- and 1,2-dibromodisilanes in the ratio of ca. 8:1 and only the 1,1,1-isomer of the tribromodisilanes. By contrast, the action of BBr₃ on Si₂H₆ gives mainly the 1,2-dibromodisilane and only the 1,1,2-isomer of tribromodisilane. These species did not show the same tendency as did the corresponding chloroderivatives to disproportionate to the more unsymmetrical forms.

The reaction of 1,1-dichlorodisilane with antimony trifluoride leads to the formation of the new fluoride, 1,1-difluorodisilane. It was not found necessary to use antimony pentachloride as catalyst as was reported for the conversion of chloro- to fluoro-monosilanes. 13

However, it appears that this is mainly an exchange reaction because SbF3 does not fluorinate disilane directly. There is appreciable cleavage of the Si-Si bond resulting in the formation of SiF₄ and also some further fluorination to give small amounts of 1,1,1trifluorodisilane, possibly by disproportionation of the difluoride.

The ¹H n.m.r. spectrum of SiH'F₂·SiH₃ (Table 1, Figure) shows the SiH₃- signal as a triplet [(IHSi-SiF) 6 Hz] of doublets [J(HSi-SiH') 2.8 Hz] centred at 3.28 p.p.m. relative to internal tetramethylsilane. The



The 'H n.m.r. spectrum of SiHF2 SiH3

SiH'- signal of a triplet [J(H'SiF) 53 Hz] of quartets is centred at 5.4 p.p.m. The spectrum is similar to that of GeH₃·SiHF₂.¹⁴ The ¹⁹F n.m.r. spectrum is also firstorder showing a doublet [J(FSiH') 53 Hz] of triplets [J(FSi-SiH') 6 Hz] centred at $-24\cdot1$ p.p.m. relative to external hexafluorobenzene. The analogous values for GeH₃·SiHF₂ were 54·5 and 8·0 Hz respectively.

The 19F n.m.r. spectrum of SiF₃·SiH₃ showed the expected quartet [J(FSiH) 5 Hz] at -41.2 p.p.m. relative to external hexafluorobenzene. Boron tribromide reacts with monochlorodisilane to give a bromine-substituted derivative without halide exchange, namely 1-bromo-1-chlorodisilane. This is confirmed by the ¹H n.m.r. spectrum of SiH'BrCl·SiH₃ in which the SiH₃- and SiH'- resonances are seen as the doublet and quartet expected for first-order H-H' coupling. The chemical shifts of the two signals, which are in the

¹¹ L. G. L. Ward and A. G. MacDiarmid, J. Inorg. Nuclear Chem., 1962, 20, 345.

12 J. Cohen, Ph.D. Thesis, University of Pennsylvania, 1967.

¹³ A. G. Maddock and H. J. Emeléus, J. Chem. Soc., 1944, D. Solan and P. L. Timms, Inorg. Chem., 1968, 7, 2157.

expected intensity ratio of 3:1, lie between those of SiHBr₂·SiH₃ and SiHCl₂·SiH₃ (Table 1).

Boron tribromide also appears to further brominate 1,1-dichlorodisilane giving 1-bromo-1,1-dichlorodisilane. The singlet at 3.80 p.p.m. in the ¹H n.m.r. spectrum of SiBrCl₃·SiH₃ lies between those of SiBr₃·SiH₃ and SiCl₃·SiH₃.

By contrast, there is no evidence that boron trichloride will readily further chlorinate mono- or 1,1dibromodisilane. However, it is a weaker halogenating agent towards the silicon hydrides, since SiH₄ is not affected by BCl₃, whereas it is brominated by BBr₃.

A tabulation of the n.m.r. parameters of the halogenodisilanes showed up some fairly consistent trends. Jensen 4 had found that the $J(^{13}C-H)$ and $J(^{29}Si-H)$ directly bonded coupling constants in methyl and monosilyl derivatives [J(MHXYZ)] can be related (1) to

$$J(MHXYZ) = J(MH_4) + A(\alpha_X + \alpha_Y + \alpha_Z) + B(\alpha_X^2 + \alpha_Y^2 + \alpha_Z^2) - C(\alpha_X\alpha_Y + \alpha_Y\alpha_Z + \alpha_Z\alpha_X)$$
 (1)

J. Chem. Soc. (A), 1970

the coupling constant in the molecule $[J(MH_4)]$ and an 'effective electronegativity' of each substituent $(\alpha_{X,Y,orZ}).$

We find that for the halogenated disilanes, as well as for all the known disilarly compounds, the same values of the constants A, B, and C (viz. 18.26, 1.78, and -1.28) can be used as for the silyl compounds. Literature values of α were utilised with the addition of: α_{SiH_a} 0.57, $\alpha_{\text{S-SiH}_s}$ -1.37, $\alpha_{\text{N(SiH}_s)_s}$ -0.72, and α_{PH_s} -0.32.* A further adjustment was made in the calculation of J(Si-H) for the silicon atom contiguous with the substituted silicon atom (2).

$$J(\text{Si-H}) = J(\text{SiH})(\text{disilane}) + 2.25\alpha$$
 (2)

There is good agreement between predicted and experimental |J| values which were generally not corrected to infinite dilution (Table 2).

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* On this scale positive values are less electronegative than hydrogen and negative values more.